

Title (en)

Coating compositions for use with an overcoated photoresist

Title (de)

Beschichtungszusammensetzungen zur Verwendung mit einem beschichteten Fotolack

Title (fr)

Compositions de revêtement destinées à être utilisées avec une résine photosensible

Publication

EP 1829942 A1 20070905 (EN)

Application

EP 07250796 A 20070226

Priority

US 7778706 P 20060228

Abstract (en)

Organic coating composition are provided including antireflective coating compositions that can reduce reflection of exposing radiation from a substrate back into an overcoated photoresist layer and/or function as a planarizing or via-fill layer. Preferred organic coating compositions of the invention comprise one or more resins that can harden upon thermal treatment without generation of a cleavage product. Particularly preferred organic coating compositions of the invention comprise one or more components that comprise anhydride and hydroxy moieties.

IPC 8 full level

C09D 133/14 (2006.01); **C09D 135/00** (2006.01); **G03F 7/00** (2006.01)

CPC (source: EP KR US)

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DOCDB simple family (application)

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